Claims

What is claimed is:

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5	1.	A power transistor device comprising:
		a substrate;
		a device film formed on the substrate; and

an adhesion layer formed on a side of the substrate opposite the device film, wherein at least a portion of the adhesion layer is at least partially segmented;

the power transistor device thereby exhibiting a reduced amount of bowing relative to an amount of bowing expected without the segmenting of the adhesion layer.

- 2. The device of claim 1, wherein the adhesion layer comprises a material selected from the group consisting of titanium, nickel and combinations comprising at least one of the foregoing materials.
- 3. The device of claim 1, wherein the adhesion layer comprises material arranged in distinct segments, each segment being at least partially separated from other segments of the adhesion layer.
- 4. The device of claim 3, wherein voids between one or more of the segments are substantially free of material.
- 5. The device of claim 3, wherein voids between one or more of the segments comprise a low stress material.
 - 6. The device of claim 5, wherein the low stress material comprises a low stress polymer.
- 7. The device of claim 1, wherein the adhesion layer comprises material arranged in distinct segments that are uniformly spaced along the adhesion layer.

- 8. The device of claim 1, wherein the adhesion layer comprises material arranged in distinct segments that are non-uniformly spaced along the adhesion layer.
- 5 9. The device of claim 1, wherein the adhesion layer comprises one or more voids, at least one of which extends partially through the adhesion layer.
 - 10. The device of claim 1, wherein the adhesion layer has a thickness of from about 100 angstroms to about 1,000 nanometers.
 - 11. The device of claim 1, further comprising at least one additional metal-containing layer associated with a side of the adhesion layer opposite the substrate.
- The device of claim 11, wherein one or more of the at least one additional metalcontaining layer is segmented.
 - 13. The device of claim 1, further comprising a barrier layer associated with a side of the adhesion layer opposite the substrate.
- 20 14. The device of claim 13, wherein the barrier layer comprises a metal selected from the group consisting of platinum, niobium and combinations comprising at least one of the foregoing metals.
- The device of claim 1, further comprising a wettable-surface layer associated with a side of the adhesion layer opposite the substrate.
 - 16. The device of claim 15, wherein the wettable-surface layer comprises a metal selected from the group consisting of gold, tin, silver, lead, germanium, bismuth, indium and combinations comprising at least one of the foregoing metals.

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17. A method of processing a power transistor device, the method comprising the steps of:

forming a device film on a substrate;

forming an adhesion layer on a side of the substrate opposite the device film; and at least partially segmenting at least a portion of the adhesion layer, the power transistor device thereby exhibiting a reduced amount of bowing relative to an amount of bowing expected without the segmenting of the adhesion layer.

18. An integrated circuit, comprising:

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at least one power transistor device comprising:

a substrate;

a device film formed on the substrate; and

an adhesion layer formed on a side of the substrate opposite the device film, wherein at least a portion of the adhesion layer is at least partially segmented;

the power transistor device thereby exhibiting a reduced amount of bowing relative to an amount of bowing expected without the segmenting of the adhesion layer.

- 19. The integrated circuit of claim 18, wherein the at least a portion of the adhesion layer is at least partially segmented by patterning along two or more intersecting axes of the power transistor device.
- 20. The integrated circuit of claim 18, wherein the adhesion layer comprises a material selected from the group consisting of titanium, nickel and combinations comprising at least one of the foregoing materials.